

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination INAO ET AL.	
		Examiner John Ruggles	Art Unit 1756	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-2002/0196420	12-2002	Naya, Masayuki	355/71
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.